



8<sup>th</sup> International Conference  
on Fundamentals and  
Applications of HIPIMS

13<sup>TH</sup> – 14<sup>TH</sup>  
JUNE 2017

BRAUNSCHWEIG

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# CONFERENCE PROGRAM

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VENUE: Fraunhofer Institute IST | Sem. 2 | Bienroder Weg 54 E | 38108 Braunschweig | DE

SUNDAY, 11<sup>TH</sup> JUNE (full day)

**SVC C-323: HIGH POWER IMPULSE MAGNETRON SPUTTERING** | Prof. A. P. Ehasarian, Sheffield Hallam University, UK ; Andre Anders, Lawrence Berkeley National Laboratory, USA

MONDAY, 12<sup>TH</sup> JUNE (½ day morning)

**SVC C-338: APPLICATION OF REACTIVE SPUTTERING** | Dr. R. Bandorf; Gerdes, H., Fraunhofer IST, Germany

MONDAY, 12<sup>TH</sup> JUNE (½ day afternoon)

**SVC C-333: PRACTICE & APPLICATIONS OF HIPIMS** | Dr. R. Bandorf, Fraunhofer IST; Prof. A. P. Ehasarian, Sheffield Hallam University, UK

## Tuesday, 13<sup>th</sup> June



### Oral Presentations

**8:00 Registration**

**8:30 Opening**

Dr. R. Bandorf, Fraunhofer IST  
Prof. A. P. Ehasarian, Sheffield Hallam University

#### Industrial cases | R. Bandorf

**9:00 Molybdenum Thin Films Deposited by High Power Impulse Magnetron Sputtering for Back Contact Applications**

Ehasarian, A. P.; Loch, D.A.L.

**9:20 On the industrialization of High Power Impulse Magnetron Sputtering**

Gajewski, W.; Róžański, P.; Zelechowski, M.; Ozimek, P.

**9:40 Pure HiPIMS Coatings with 2 µm/hour for Cutting Tool Coatings**

Leyendecker, T.; Lemmer, O.; Kölker, W.; Schiffers, Ch.

**10:00 Coffee break**

#### Fundamental aspects of HIPIMS | Prof. A. P. Ehasarian

**10:20 Correlation of spatially resolved in-vacuum XPS characterisation and optical diagnostic for magnetron targets in HIPIMS plasma**

Layes, V.; Monje, S.; Corbella, C.; Schutz von der Gathen, V.; von Keudell, A.; de los Arcos, T.

**10:40 Simulation of heating of the target during High Power Impulse Magnetron Sputtering**

Karzin, V.V.; Karapets, K.I.

**11:00 Study of spoke rotation, merging and splitting in HiPIMS plasma**

Klein, P.; Hnilica, J.; Lockwood-Estrin, F.; Vašina, P.; Bradley, J. W.

**11:20 Potential Structure of Ionization Zones and Implications for Electron Heating and Ionization Dynamics**

Anders, A.; Panjan, M.

**11:40 Conference Photograph**

**12:00 Lunch**

#### Cathode configuration & operation modes | Jaroslav Vlcek

**13:00 Synchronised external magnetic fields applied in HiPIMS enhance plasma generation and plasma transport**

Bilek, M.; Ganesan, R.; Bathgate, S.; McKenzie, D.R.

**13:20 Effects of Bipolar Pulses in High Powered Impulse Magnetron Sputtering (HiPIMS)**

Ruzic, D. N.; Haehnlein, I.; McLain, J.; Shchelkanov, I.

**13:40 Improve the Coating Properties by Modeling and Optimizing the HiPIMS Magnetron Configuration**

Luo, H.; Gao, F.; Billard, A.

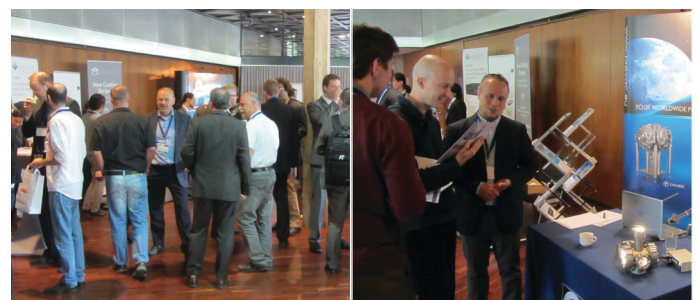
**14:00 Unrevealed process enhancements by engaging an Active Positive Voltage reversal in HiPIMS applications**

Eichenhofer, G.; Fernández, I.; Wennberg, A.

**14:20 Improving deposition rate of titanium nitride-based films using a superimposed high-power impulse and middle-frequency magnetron sputtering technique**

Diyatmika, W.; Lee, J.-W.

**14:40 Coffee break**







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## 15:00 Guided Postersession

1 Slide per poster, max. time for poster introduction: 1 min

- P 1 A controlled high-rate reactive HiPIMS deposition of ZrO<sub>2</sub> films: an optical emission spectroscopy study**  
Pajdarová, A.D.; Vlček, J.
- P 2 Calorimetric study of secondary electron in sputtering and nitriding PIII process**  
Haase, F.; Manova, D.; Mändl, S.; Kersten, H.
- P 3 The Thermal Oxidation of TiAlN High Power Impulse Magnetron Sputtering Hard Coatings as Revealed by Combined Ion and Electron Spectroscopy**  
Wiesing, M.; de los Arcos, T.; Grundmeier, G.
- P 4 Raman spectroscopy of titanium nitride films deposited by reactive magnetron sputtering with a hot target**  
Komlev, A. A.; Levitskii, V. S.; Shapovalov, V. I.; Smirnov, V. V.; Shutova, E.S.
- P 5 Oxynitrides films model synthesis by the high power reactive sputtering technique**  
Komlev, A. A.; Zav'alov, A. V.; Shapovalov, V. I.; Minzhulina, E. A.; Morozova, A. A.
- P 6 Non-contact method of temperature measuring of target surface in high power magnetron sputtering**  
Komlev, A. E.; Komlev, A. A.; Uhov, A.A.; Shutova, E.S.
- P 7 Crystalline deposition of GaN and ternary compounds by Pulsed Sputter Deposition of GaN**  
Steib, F.; Gülink, J.; Kossev, I.; Ledig, J.; Remmele, T.; Behres, A.; Fündling, S.; Albrecht, M.; Heicke, S.; Müller, T.; Straßburg, M.; Lugauer, H.-J.; Wehmann, H.-H.; Waag, A.
- P 8 HPMF process of Al-doped zinc oxide films from rotatable targets**  
Sittinger, V.; Jung, S.; Britze, C.; Gerdes, H.; Schorn, D.; Wallendorf, T.; Bräuer, G.

- P 9 The effect of annealing on mechanical properties and constitution of TiC:H and TiC/a-C:H thin films deposited by high power impulse magnetron sputtering**  
Poltorak, Ch.; Leiste, H.; Mikulla, Ch.; Rinke, M.; Wantzen, K.; Pavlides, C.; Burger, W.; Albers, A.; Stüber, M.; Ulrich, S.
- P 10 Measuring the Ionized Fraction of Film Forming species**  
Gerdes, H.; Spreemann, D.; Bandorf, R.; Vergöhl, M.; Bräuer, G.
- P 11 Metal-doped DLC layers prepared by HIPIMS/PECVD**  
Grein, M.; Bandorf, R.; Bräuer, G.
- P 12 Investigation of the ion to neutral ratio by plasma emission monitoring using metallic and reactive HIPIMS process**  
Rieke, J.; Gerdes, H.; Bandorf, R.; Schütte, T.; Vergöhl, M.; Bräuer, G.
- P 13 Coatings for Friction Stir Welding Applications**  
Ehiasarian, A.
- P 14 Influence of ion-to-metal flux ratio on the mechanical and tribological properties of TiN coatings deposited by HiPIMS**  
Tiron, V.; Velicu, I.-L.; Lupu, N.; Cristea, D.; Stoian, G.; Munteanu, D.
- P 15 Velocity distribution of sputtered species in the ionization region**  
Held, J.; Hecimovic, A.; Schulz-von der Gathen, V.
- P 16 High mobility amorphous zinc oxynitride films deposited by reactive HiPIMS**  
Ganesan, R.; Akhava, B.; McKenzie, D. R.; Bilek, M. M. M.; Thorwarth, K.; Hug, H.-J.
- P17 Effect of chamber environment on defect generation and their influence on corrosion and tribological properties of HIPIMS deposited CrN/NbN Coatings**  
Biswas, B.; Hovsepian, P. Eh.

17:00 End of the scientific program



## 18:00 Networking Event with Awards Ceremony

Location: »Dornse« at Altstadttrahaus



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## Wednesday, 14<sup>th</sup> June



### Oral Presentations

8:00 Admittance

#### Reactive HIPIMS | P. Hovsepien

8:40 **An ionization region model of the reactive Ar/O<sub>2</sub> high power impulse magnetron sputtering discharge**

Gudmundsson, J. T.; Lundin, D.; Brennig, N.; Raadu, M. A.; Huo, Ch.; Minea, T. M.

9:00 **The role of metal implantation in reactive high power impulse magnetron sputtering**

Kozak, T.; Vlcek, J.

9:20 **r-HiPIMS of magnesium oxide**

Moens, F.; Konstantinidis, S.; Depla, D.

9:40 **High-rate reactive HiPIMS deposition of Hf-O-N films with smoothly controlled composition**

Vlček, J.; Belosludtsev, A.; Houška, J.; Rezek, J.

10:00 **The target condition dependent optical and electronic functionalities of WO<sub>3</sub> and WO<sub>x</sub>Ny films deposited by reactive HiPIMS**

Ganesan, R.; Akhavan, B.; McKenzie, D. R.; Bilek, M. M. M.

10:20 **HiPIMS Peak Power to Affect Film Adhesion of Titanium and Titanium Oxide Films on PET Substrate**

He, J.-L.; Chen, M.-Y.; Chen, Y.-H.

10:40 Coffee break

#### Hard coatings | Prof. G. Bräuer

11:00 **Measurements on a high voltage pulsed substrate (PBII) in a HiPIMS process**

Gauter, S.; Fröhlich, M.; Garkas, W.; Polak, M.; Kersten, H.

11:20 **HiPIMS coatings for SRF cavities: influence of process parameters on film morphology and cavities performances**

Rosaz, G.; Aull, S.; Calatroni, S.; Richard, T.; Sublet, A.; Taborelli, M.; Venturini-Delsolaro, W.

11:40 **HiPIMS deposited CrN/NbN coatings to preserve the mechanical properties of the substrate material and protect against steam oxidation and water droplet erosion attacks**

Hovsepien, P. E.; Ehasarian, A. P.; Purandare, Y. P.; Mayr, P.; Abstoss, K. G.; Schulz, W.; Kranzmann, A.

12:00 **Phenomenological study of the influence of HiPIMS process parameters on the tribomechanical properties of TiAlN coatings**

Tillmann, W.; Grisales, D.; Stangier, D.

12:20 **Adhesion enhancement of DLC hard coatings by HiPIMS metal etching: a comparison between Titanium and Chromium**

Santiago, J. A.; Fernandez-Martínez, I.; Monclús, M.; Molina, J.; Gonzalez-Arrabal, R.; Sanchez-Lopez, J. C.; Rojas, C.; Wennberg, A.

12:40 **HiPIMS-Arc carbon films on 500 mm cathodes**

Bandorf, R.; Rösler, J.; Gerdes, H.; Bräuer, G.

13:00 **Closing Remarks**

Bandorf, R.

13:10 Lunch & End of Conference

### INFORMATION FOR EXHIBITORS

**Setup** starts on Monday 12<sup>th</sup> June 2017 from 3 p.m. to 5 p.m. | **Dismantling** starts on Wednesday 14<sup>th</sup> June 2017 from 2 p.m. (after lunch)

**Time and contact information for delivery of exhibition material:**

Stadthalle Braunschweig | Leonhardplatz | 38102 Braunschweig | Germany

Earliest date for arrivals of your exhibition material:

**6<sup>th</sup> June 2017, keyword »HIPIMS 2017«**